

**SiO<sub>2</sub> Thickness Measurement Before & After RIE**

Sample No.	CF <sub>4</sub> Gas Flow	O <sub>2</sub> Gas Flow Time	Time (min)	Power (W)	First round etching			Second round etching		
					Before RIE (nm)	After RIE (nm)	Etch Rate (nm)	Before RIE (nm)	After RIE (nm)	Etch Rate (nm)
1	40	5	0.5	100	875	853	44	853	806.67	92.67
2	40	5	1	100	875	794	81	794	706	88
3	40	5	1.5	100	875	741	89.33	741	605	90.67
4	40	5	2	100	875	695	90	695	517.5	88.75
5	40	10	0.5	100	885	845	80	845	794	102
6	40	10	1	100	885	798	87	798	697.33	100.67
7	40	10	1.5	100	885	737	98.7	737	577.75	106.17
8	40	10	2	100	885	684	100.5	684	505.5	89.25